

FIG. 1

1/13

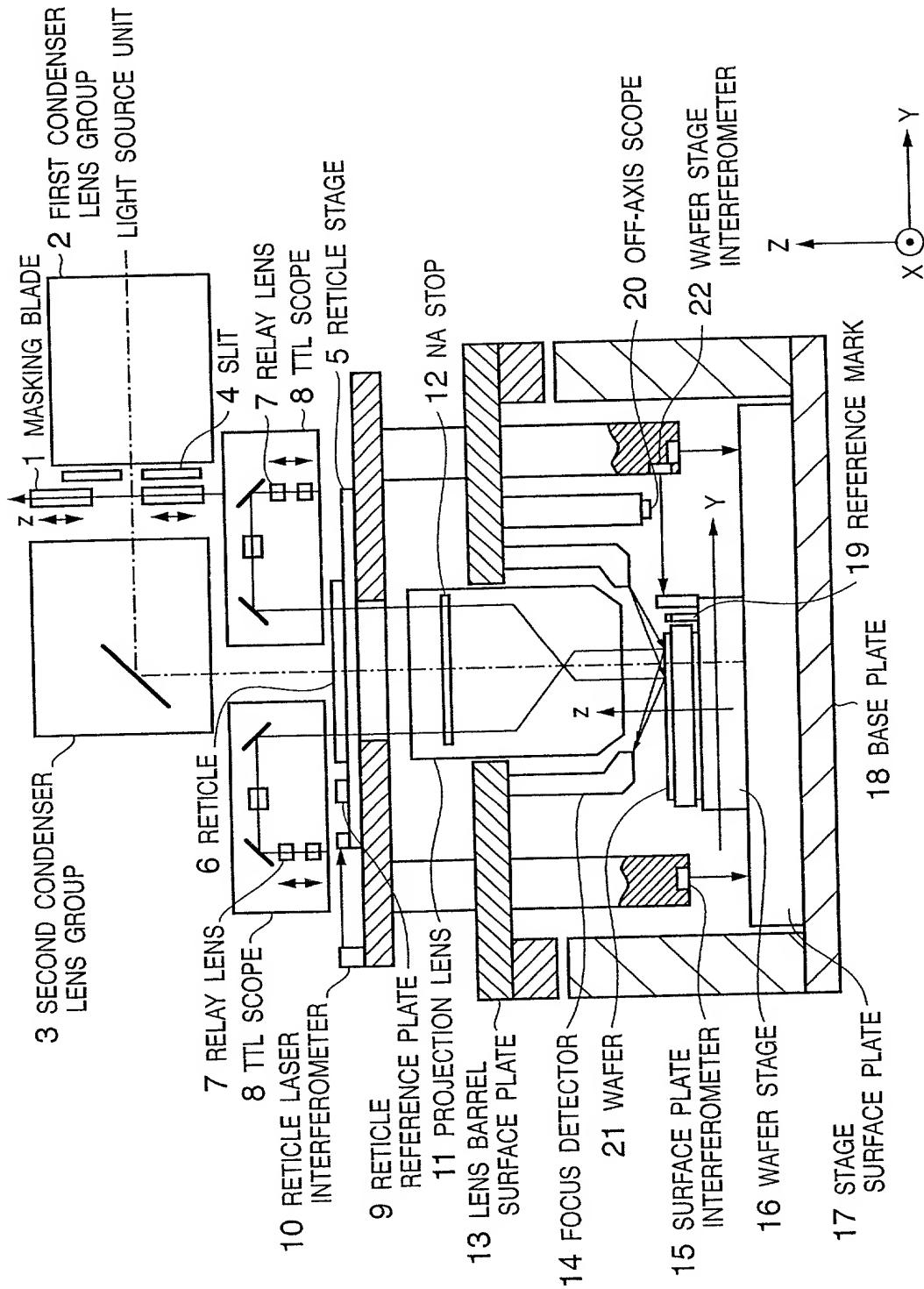


FIG. 2

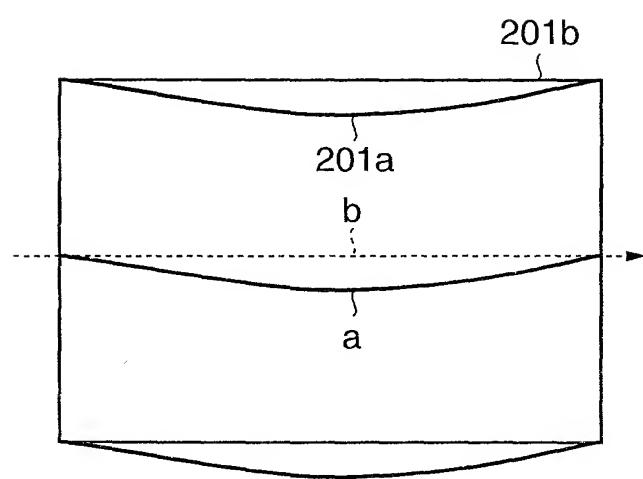


FIG. 3

3/13

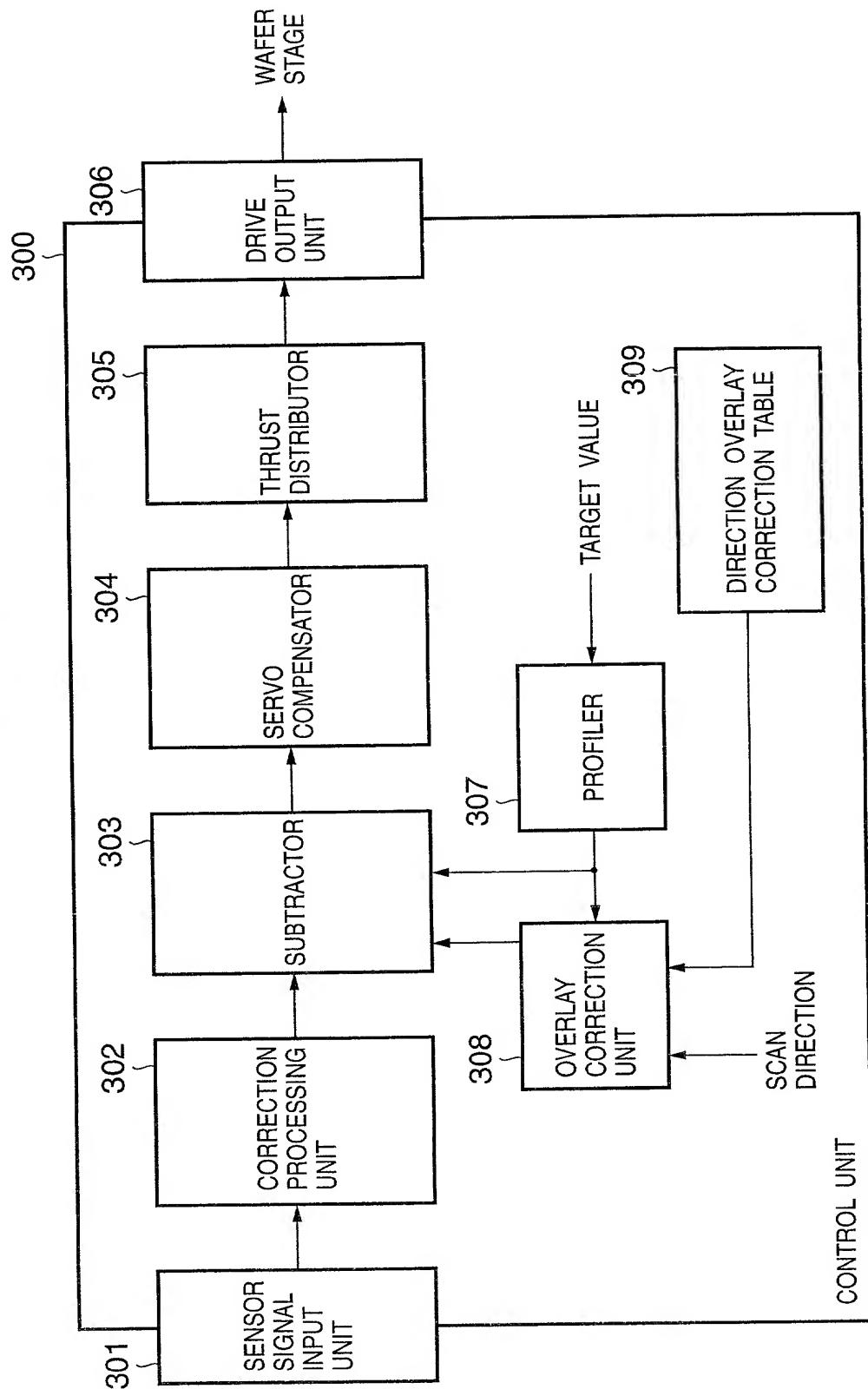


FIG. 4

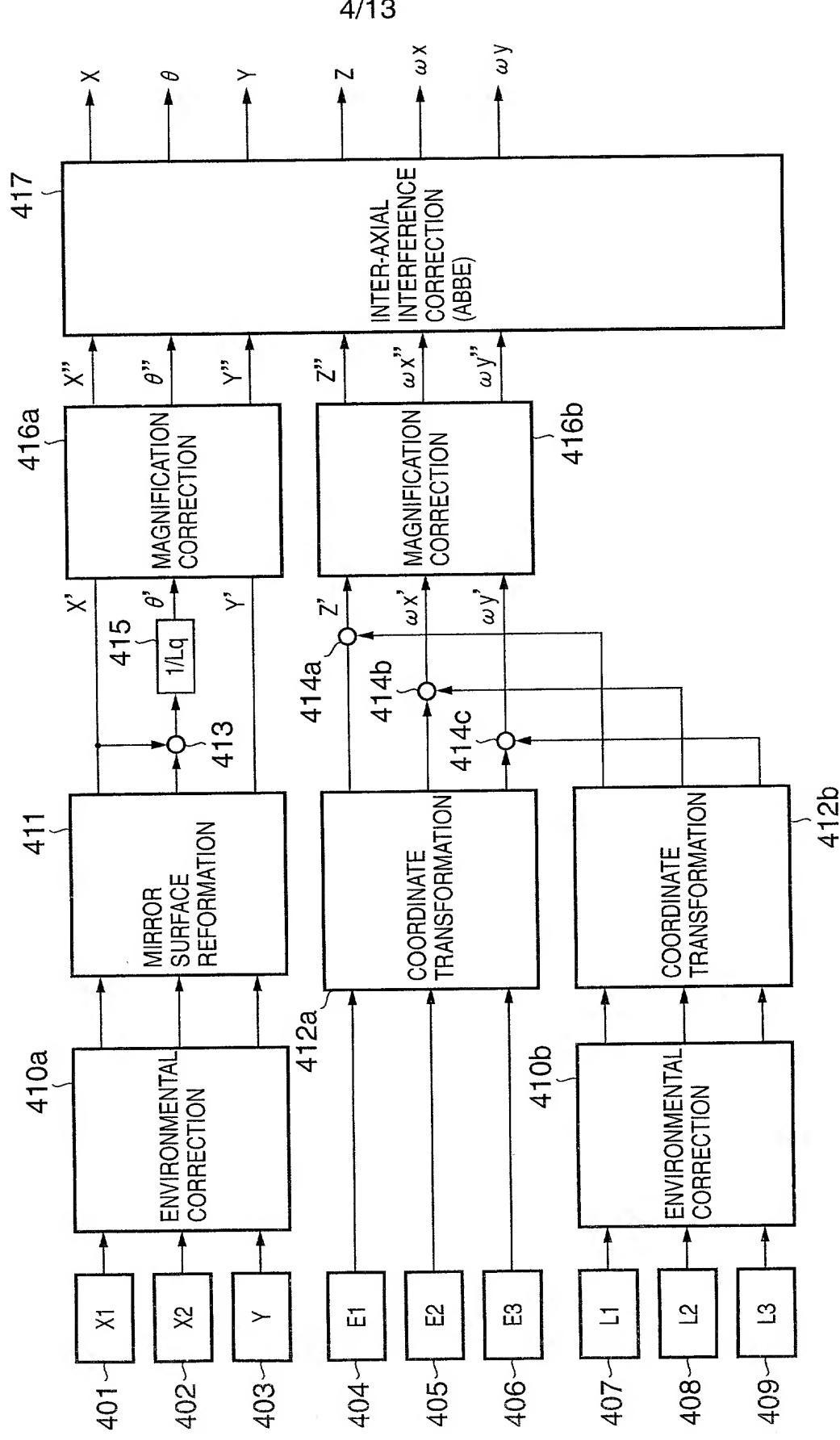


FIG. 5

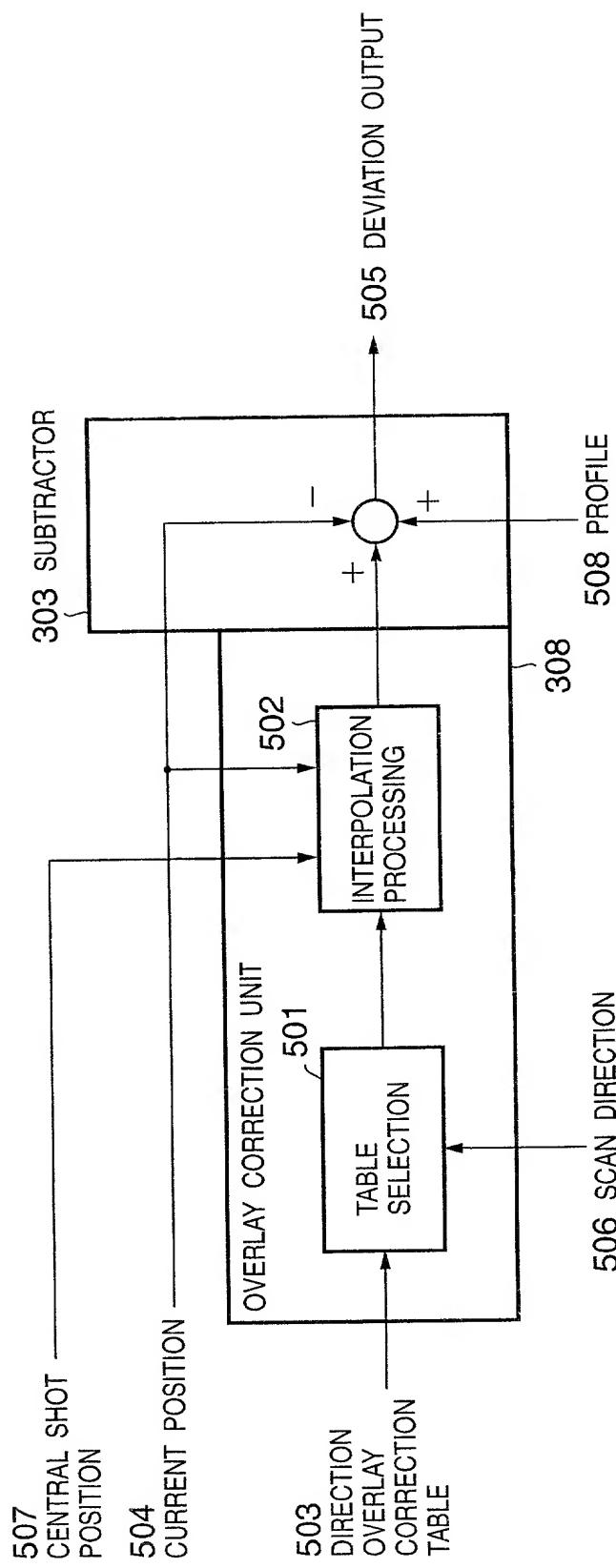


FIG. 6

ORIGIN INTERVAL	-16.000 4.000		[mm] [mm]		
CORRECTION DATA (FORWARD)			[nm/pbb]		
X	Y	Z	Qx	Qy	Qz
5	1	10	0	-10	20
4	1	8	10	-10	10
2	0	10	20	20	10
1	-1	12	20	40	10
-1	-4	13	20	30	0
-4	-2	10	40	40	-10
-3	-4	7	10	50	-30
-6	-5	4	0	80	-30
-12	-9	0	-20	60	-40
(REVERSE)					
X	Y	Z	Qx	Qy	Qz
4	0	9	10	-10	20
2	0	6	0	0	10
0	-1	11	10	10	10
0	-1	11	20	30	20
-3	-4	10	40	10	0
-5	-3	9	20	40	-10
-5	-4	6	20	60	-30
-7	-5	4	10	100	-30
-14	-9	-1	0	80	-30

7/13

FIG. 7

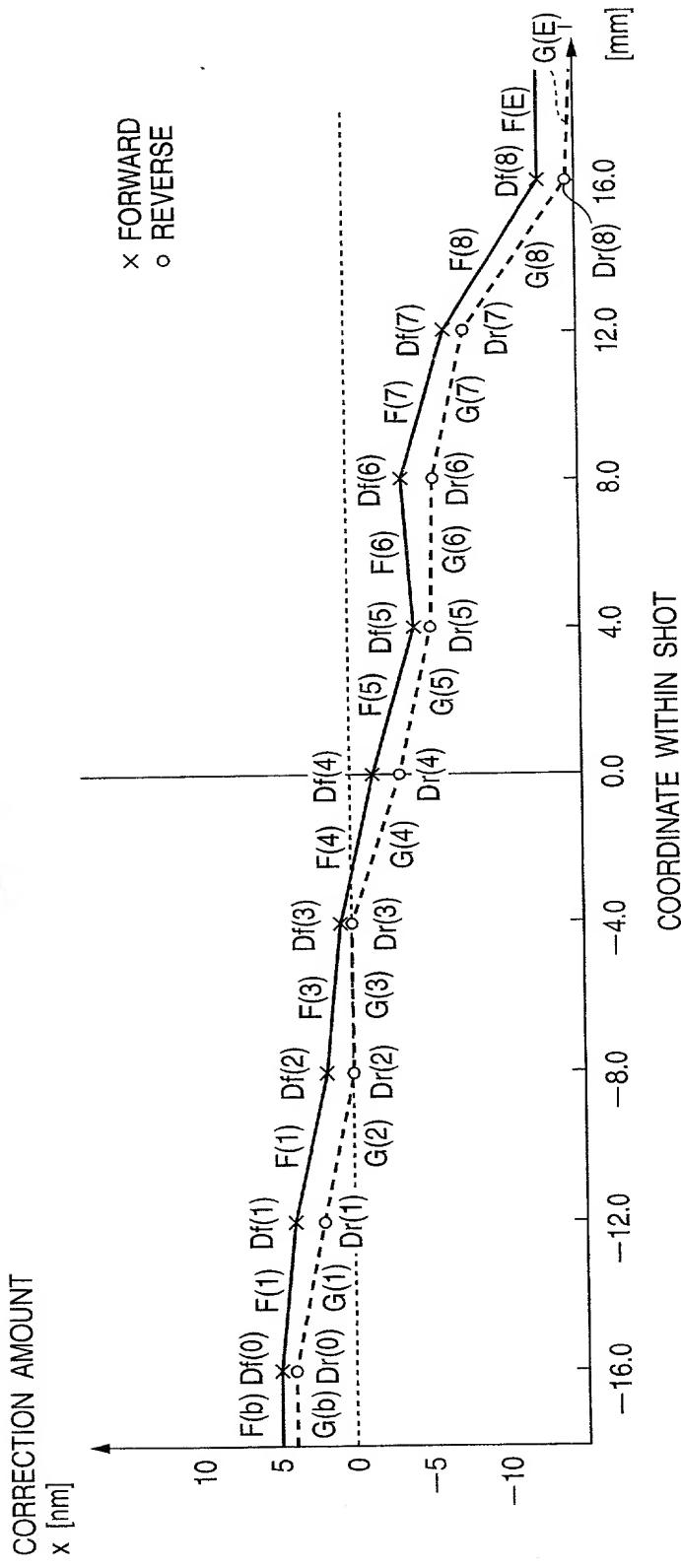
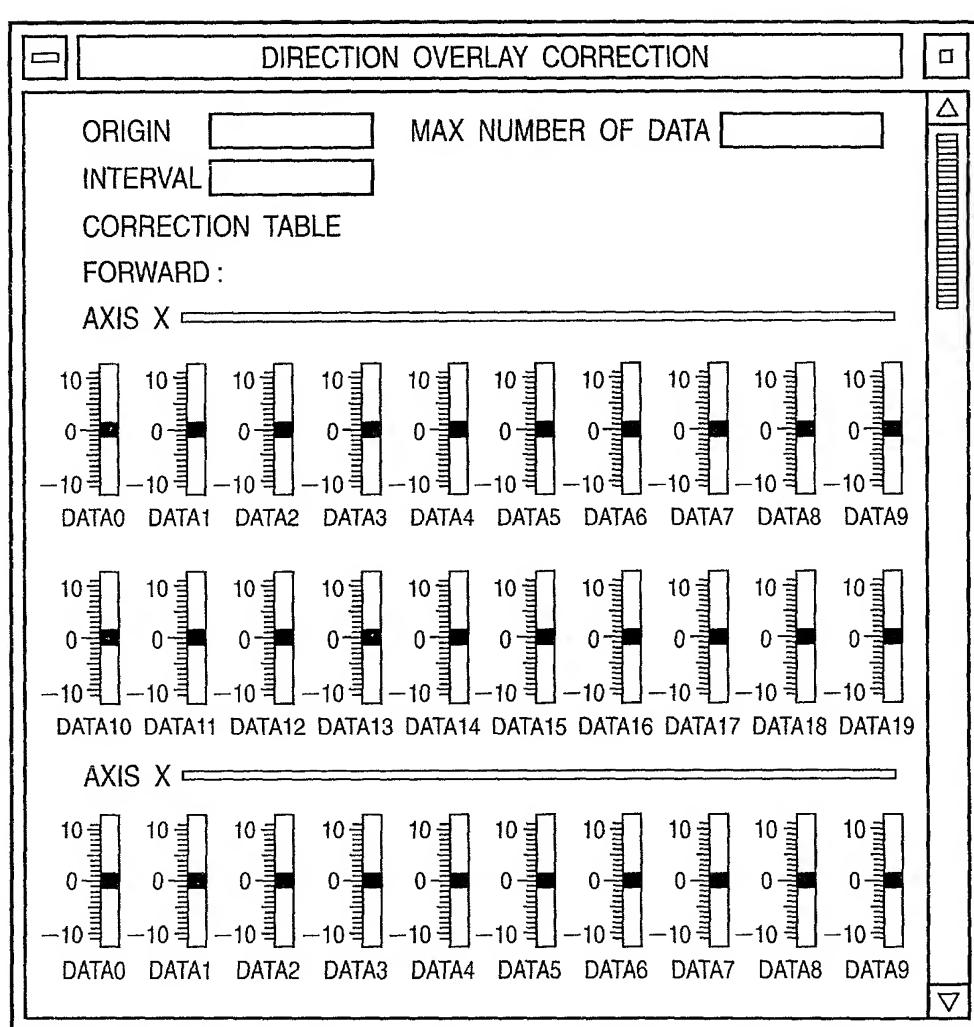


FIG. 8



1001

9/13

FIG. 9

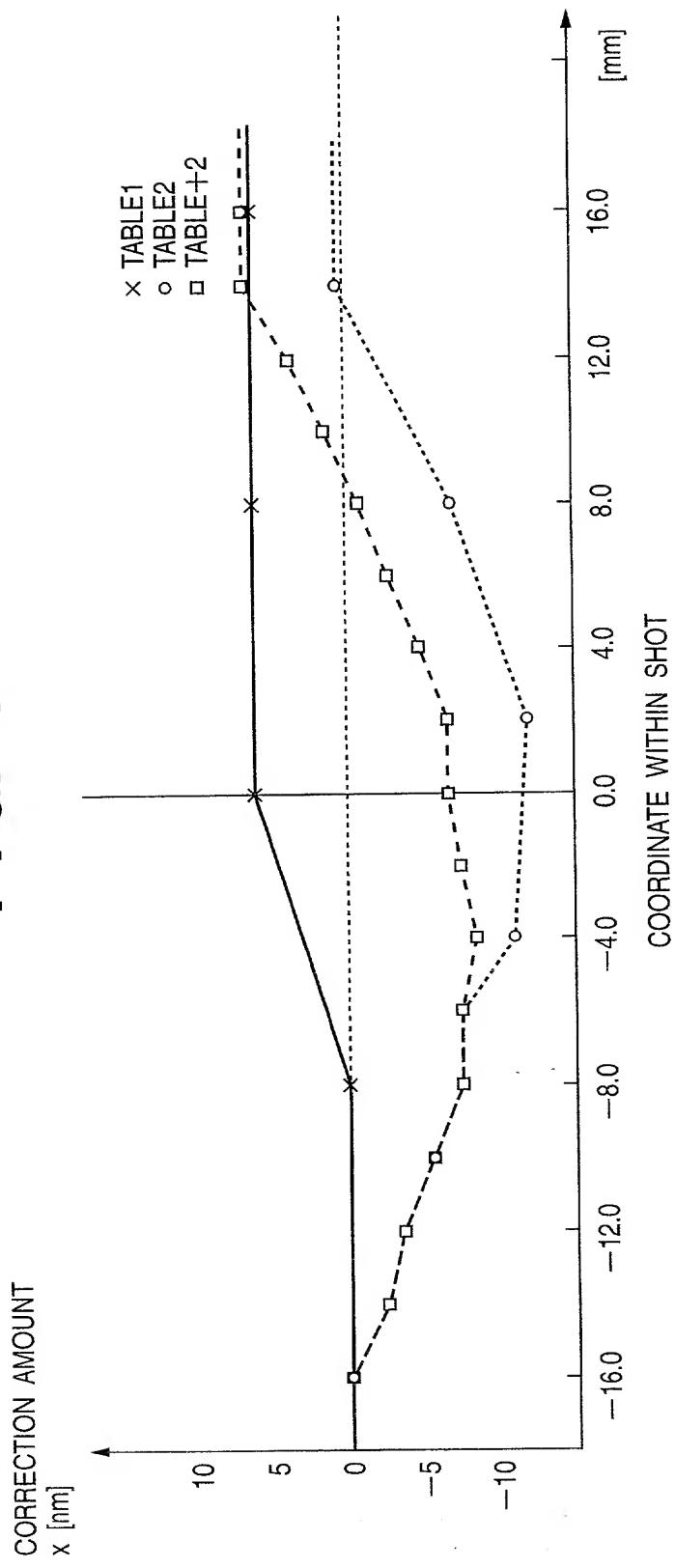


FIG. 10

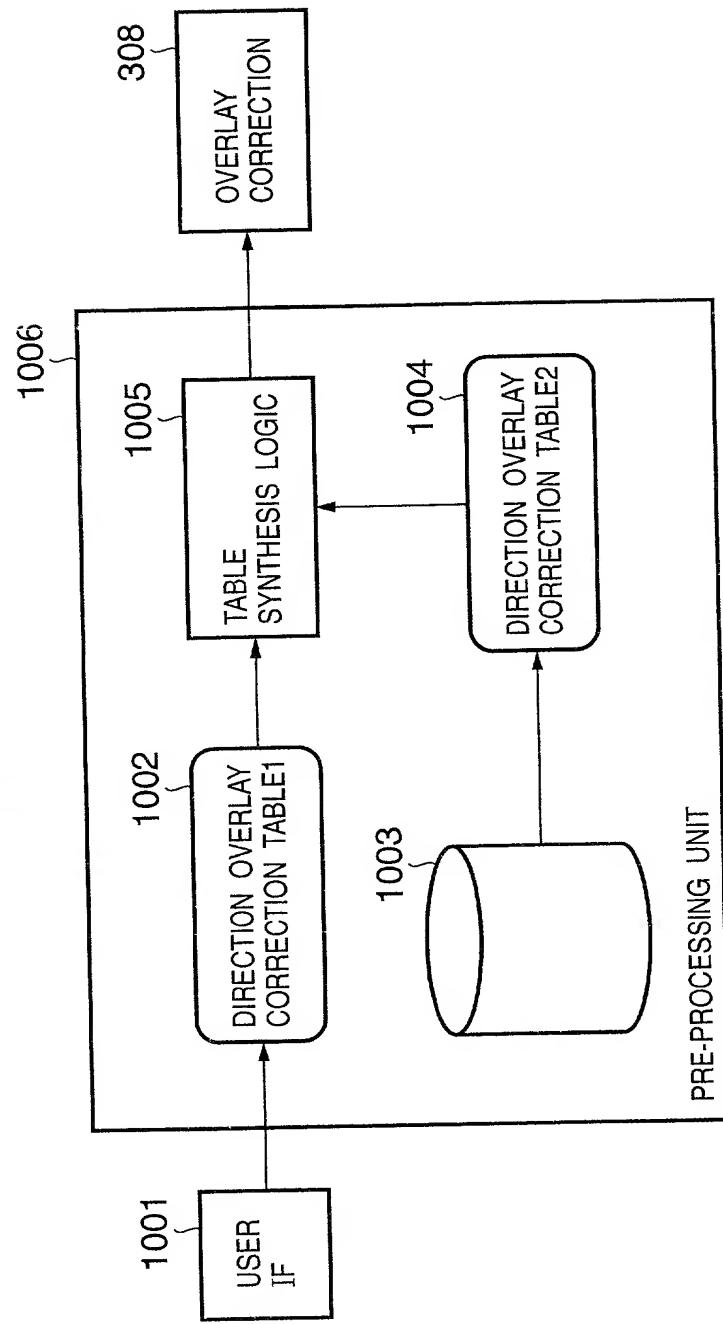


FIG. 11

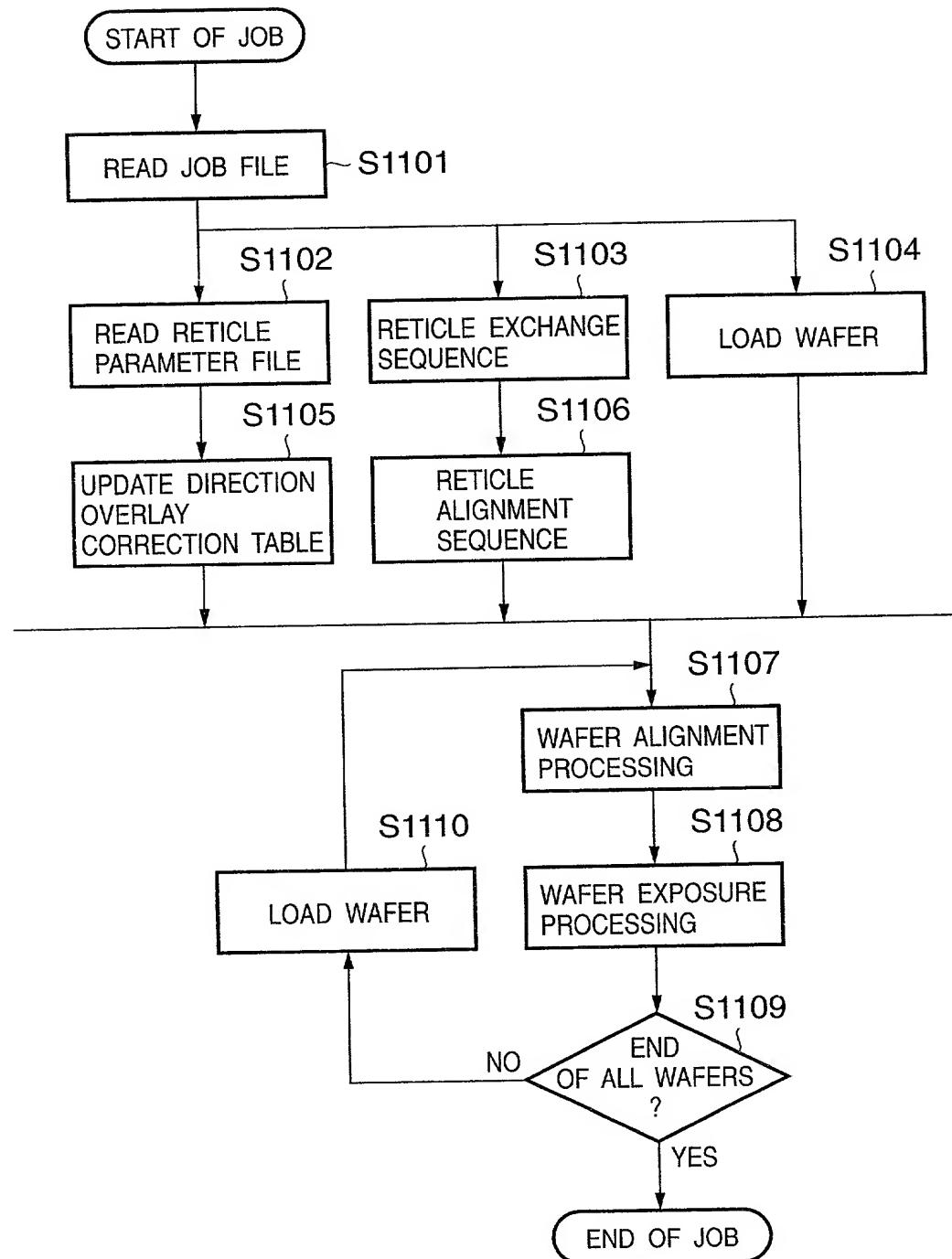
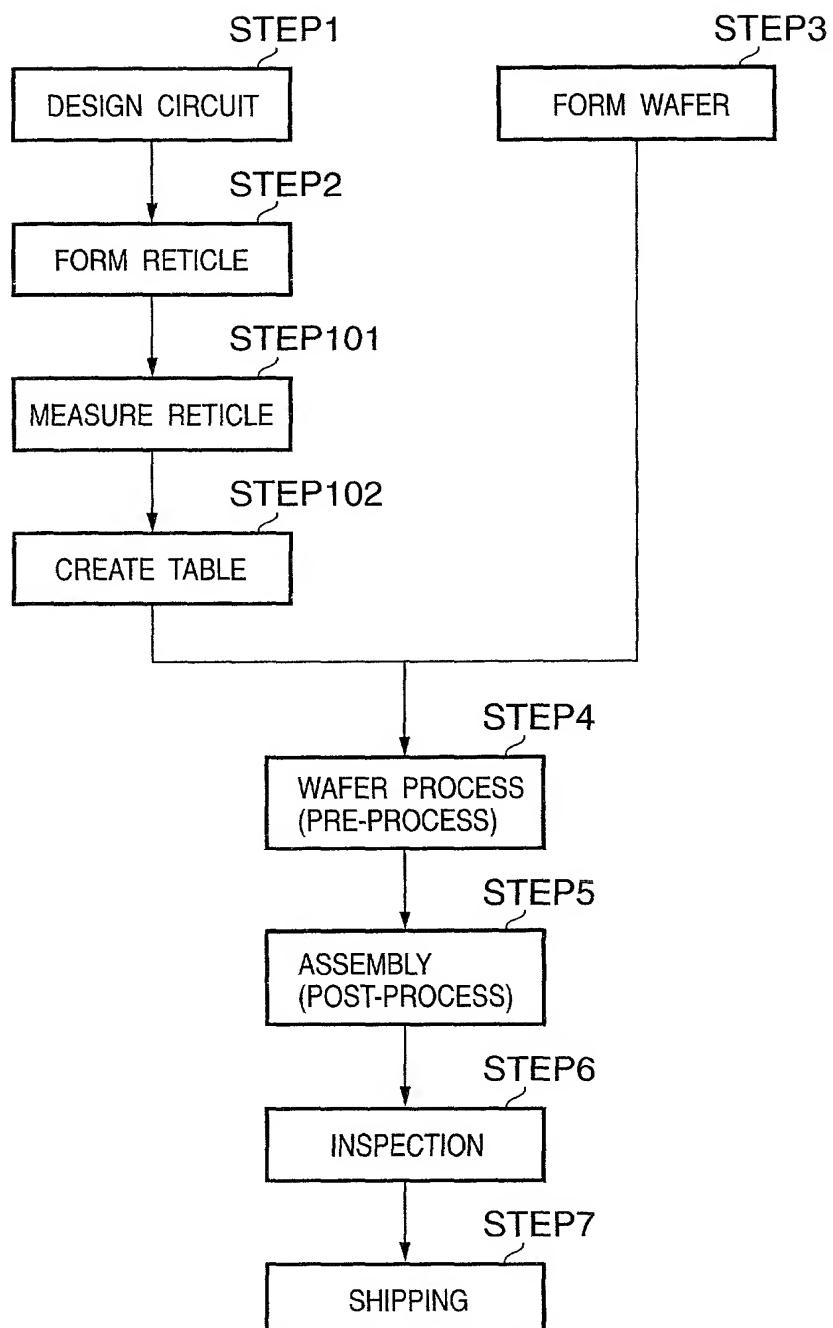


FIG. 12

10050594 - 011802



SEMICONDUCTOR DEVICE MANUFACTURING FLOW

FIG. 13